				Time stamp
Number [Hits	Search Text	DB	2002/04/03 10:14
Number	CEE	(439/592) CCLS	USPAT USPAT	2002/04/03 10:17
	105	(//20/502) CCIS) and ((tin (ti titanium)	USPAT	2002/04/03 10:11
-	1	- 4: -:+ -: dol came (w tungsten co condit)	USPAT	2002/04/02 13:01
į	9420	(Jules of the principle of the control of the contr	USPAI	2002/01/02 10:01
	3.20	tantalum titanium tungsten w aluminum al/		
	į	near3 (nitride\$1 oxy\$1nitride\$1)) tin aln		
		tan tion)	,,,,,,,,,,,,,,,,,,,,,,,,,,,,,,,,,,,,,,	2002/04/02 13:03
	1720	(/diffusion harrier) same (((metal\$3 ta ti	USPAT	2002/04/02 10:00
	1.20	tentalum titanium tungsten W aluminum al)		
		/nitride\$1 oxv\$lnitride\$1)) Lill dill		
		tan tion)) and (fsg bpsg psg bsg silicate		1
		-d÷ aloce\$? siof)		2002/04/02 13:14
	1790	((Metal)) ta	USPAT	2002/04/02 13:21
-	1.50	Li tantalum titanium tungsten w aluminum		
		-1) noar3 (nitrideS] OXV\$INITTIGE\$1// CIN		
		-1- top tion)) and (doped adl (OXIGERI		
		diovide(1))) (((diffusion parrier) same		
	1	l///matalea ta ti tantalum titanium		
		tungston W aluminum all nears (nitrides)		
		cinitride(1)) tin alm tam tion)) and	į	
		(fsg bpsg psg bsg silicate adj glass\$2		
		-: a f \ \		2002/04/02 13:20
	1770	1 ///a:ffucion barrier) same ((metala) ta	USPAT	2002/04/02 13:20
-	1//0	le: toptolum titanium tundsten w diuminum	1	
		1 -1, nonz /nitrideSl OXVSINITTIGEFI// CIM	i	
		lain tan tion)) and (doped adl (Oxideri	İ	
		dioxide\$1))) (((diffusion barrier) same	ì	1
		1 ///matalea ta ti tantalum titanium	İ	Ì
	ļ	tungsten W aluminum al) near3 (nitride\$1		
		oxy\$lnitride\$1)) tin aln tan tion)) and		
		(fsg bpsg psg bsg silicate adj glass\$2	ł	
	1	(isg bpsg psg bsg silleds) thick\$4 siof))) and (temperature\$1 thick\$4		
		pressure\$1 plasma power rf frequenc\$3)		
			USPAT	2002/04/02 13:3
-	1237		USPAT	2002/04/02 17:2
-	262	ti tantalum titanium tungsten W aluminum		
		al) near3 (nitride\$1 oxy\$1nitride\$1)) tin		
		al) near3 (hitrides) Oxygination () aln tan tion)) and (doped adj (oxides)		
		dioxide\$1))) (((diffusion barrier) same		ļ
		dioxide\$1))) ((diffusion baffles) ((metal\$3 ta ti tantalum titanium		
		(((metal\$3 td tl tantalam tream tride\$1 tungsten W aluminum al) near3 (nitride\$1		
		oxy\$lnitride\$1)) tin aln tan tion)) and		
		(fsg bpsg psg bsg silicate adj glass\$2		į
		(fsg bpsg psg bsg silicate thicks4 siof))) and (temperature\$1 thick\$4		
		pressure\$1 plasma power of frequenc\$3))		
		and ((438/627, 628, 643, 644, 653, 654). CCLS.)		
			USPAT	2002/04/02 17:3
_	7933	(((metal\$3 ta ti tantalum titumtum		
	1	tungsten W aluminum al) near3 (nitride\$1 oxy\$1nitride\$1)) tin aln tan tion) and		
		oxy\$1nitride\$1)) tin all tan tion, and ((doped near3 (oxide\$1 dioxide\$1 glass\$2)		
	ļ	((doped near) (oxide) dioxidevi grassia,		
) bsg bpsg fsg siof psg) O (((metal\$3 ta ti tantalum titanium	USPAT	2002/04/02 17:
-	- (tungsten W aluminum al) near3 (nitride\$1		Ì
		tungsten w aluminum all hears (hierard) and		
		oxy\$1nitride\$1)) tin aln tan tion) and		
		((doped near3 (oxide\$1 dioxide\$1 glass\$2)		
ļ) bsg bpsg fsg siof psg)) and (
1		(((metal\$3 ta ti tantalum titanium		
	ļ	tungsten W aluminum al) near3 (nitride\$1	·	
		cinitride\$1\\ tin all tan tion; same		
	1	//- nitrogen) near? rich nearz pidsma//	USPAT	2002/04/02 17:
_	10	A / //matales ta ti tantalum tilduium		
	1	the matter W aluminum all nears (NILLIAE)		
		1cimit mide(1)) tin ain tan tion, and		
		//doped near3 (Oxide\$1 dlox1de\$1 glass*2)		
	1) had been fed siof psq)) and (
		l tantalim ficanium	,	1
	1	l lumeton Waluminum all nears (NILLIGEY	.	
		lovicinitrides])) tin ain tan tion, same		
1		((n nitrogen) near10 plasma))	L	
		(III III CIOGOLI, III CI II		

[-	104	(((((metal\$3 ta ti tantalum titanium	USPAT	2002/04/02 17:50
1	İ	tungsten W aluminum al) near3 (nitride\$1	ļ	
	ļ	oxy\$1nitride\$1)) tin aln tan tion) and		
1]	((doped near3 (oxide\$1 dioxide\$1 glass\$2)		
) bsg bpsg fsg siof psg)) and (
1		(((metal\$3 ta ti tantalum titanium		
		tungsten W aluminum al) near3 (nitride\$1		
		oxy\$1nitride\$1)) tin aln tan tion) same		
		((n nitrogen) near10 plasma))) and (
1		(((metal\$3 ta ti tantalum titanium		
		tungsten W aluminum al) near3 (nitride\$1		
		oxy\$1nitride\$1)) tin aln tan tion) same		
		((n nitrogen) near10 plasma))		
-	81		USPAT	2002/04/02 17:52
		tungsten W aluminum al) near3 (nitride\$1		
		oxy\$1nitride\$1)) tin aln tan tion) and		1
		((doped near3 (oxide\$1 dioxide\$1 glass\$2)		
) bsg bpsg fsg siof psg)) and (
		(((metal\$3 ta ti tantalum titanium		
		tungsten W aluminum al) near3 (nitride\$1		
		oxy\$1nitride\$1)) tin aln tan tion) same		
		((n nitrogen) near10 plasma))) and (
		(((metal\$3 ta ti tantalum titanium		
		tungsten W aluminum al) near3 (nitride\$1		
		oxy\$1nitride\$1)) tin aln tan tion) same		
1		((n nitrogen) near10 plasma))) and ((temperature pressure thick thickness rf		
-		frequenc\$3 power watt\$1) same ((n		
		nitrogen) near10 plasma))		
1	1	III (I O de II) II e a t I o b t a 2 iii a)		